INFORMATION DISCLOSURE CITATION

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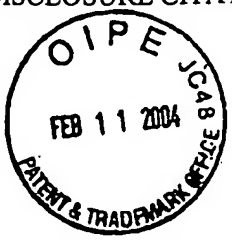

Docket: 015559-282	Appln. No.: 10/658,042
Applicant: Shuwen Guo	
Filed: September 9, 2003	Group: 2878

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Examiner		Document No.	Date	Name	Class	Sub	
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CH		Hsieh, Ming-Chin et al., "Design and Fabrication of a Novel Crystal SiGeC Far Infrared Sensor with Wavelength 8-14 Micrometer," IEEE Sensors Journal, Vol. 2, No. 4, pp. 360-365 (08/2002)
CH		Taniguchi, Y. et al., "Pyroelectric Infrared Sensor Using PZT Thin Plate on Diaphragm as Sensitive Elements," Electronics and Communications in Japan, Part 2, Vol. 79, No. 7, pp. 86-96 (01/1996)
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CH		Lahiji, G.R. et al., "A Batch-Fabricated Silicon Thermopile Infrared Detector," IEEE Transactions on Electron Devices, Vol. ED-29, No. 1, pp. 14-22 (01/1982)
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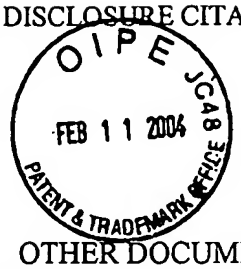

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CH		"CYCLOTENE – Advanced Electronics Resins Processing Procedures for Dry-Etch CYCLOTENE Advanced Electronics Resins (Dry-Etch BCB)," pp. 1-8, by The Dow Chemical Company (1997)
CH		Web page relating to "CYCLOTENE Dry-Etch Resins," by The Dow Chemical Company (date of first publication unknown) Applicants admit the status of this publication as prior art for the limited purpose of examination of this application, but otherwise reserve the right to challenge the status of this publication as prior art.
CH		Web page relating to "CYCLOTENE Planarization," by The Dow Chemical Company (date of first publication unknown) Applicants admit the status of this publication as prior art for the limited purpose of examination of this application, but otherwise reserve the right to challenge the status of this publication as prior art.
CH		Web page relating to "CYCLOTENE Plasma Etching," by The Dow Chemical Company (date of first publication unknown) Applicants admit the status of this publication as prior art for the limited purpose of examination of this application, but otherwise reserve the right to challenge the status of this publication as prior art.

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